



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR
REMOVING PHOTORESIST AND/OR
RESIST RESIDUE AT PRESSURES
RANGING FROM AMBIENT TO
SUPERCRITICAL

Confirmation No.: 8934

Group Art Unit: 1746

Examiner: Bibi Sharidan Carrillo

**RESPONSE TO FINAL OFFICE ACTION
MAILED JANUARY 4, 2005**

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M/S RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited
with the United States Postal Service as First Class Mail in an
envelope, addressed to: Commissioner for Patents, P.O.
Box 1450, Alexandria, VA 22313-1450 on May 3, 2005.
STALLMAN & POLLOCK LLP

Dated: 05/3/2005

By:


Georgia K. Stith

Sir:

In response to the Final Office Action mailed January 4, 2005, and in accordance with the
accompanying **Request for Continued Examination** and One-Month Extension of Time, please
amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this
paper.

Remarks/Arguments begin on page 10 of this paper.

05/06/2005 WASFAW1 00000044 10620895

02 FC:2251

60.00 OP

Atty Docket No.: SCP-9410